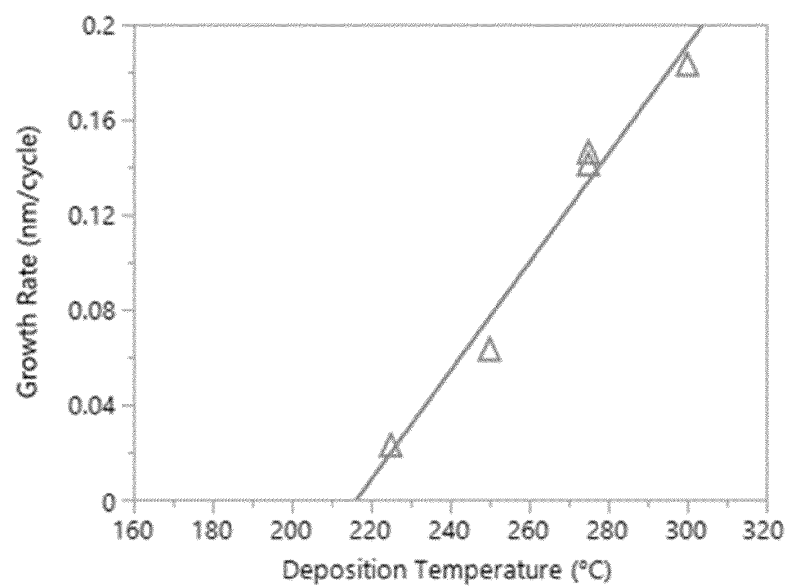


1/12

Thermal Decomposition Trend of (DMBD)Ru(CO)₃ on SiO₂**FIG. 1**

2/12

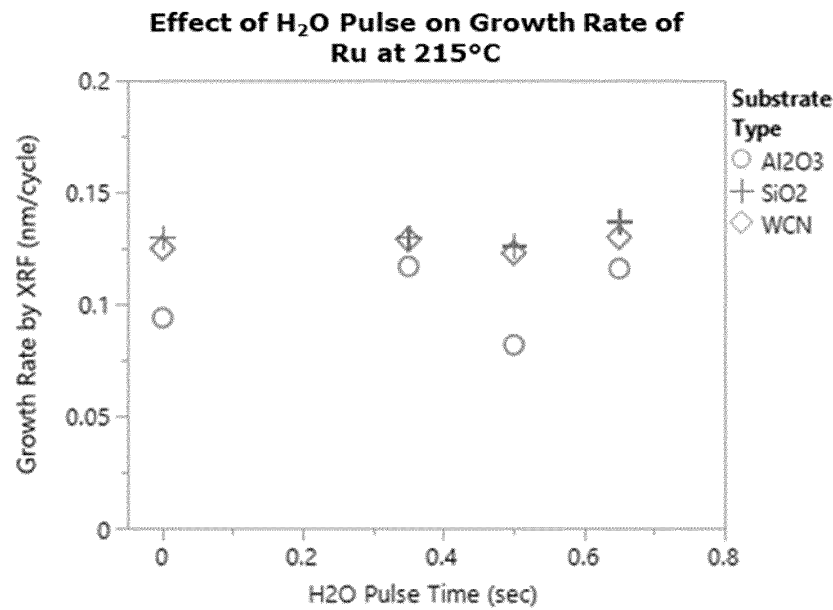


FIG. 2A

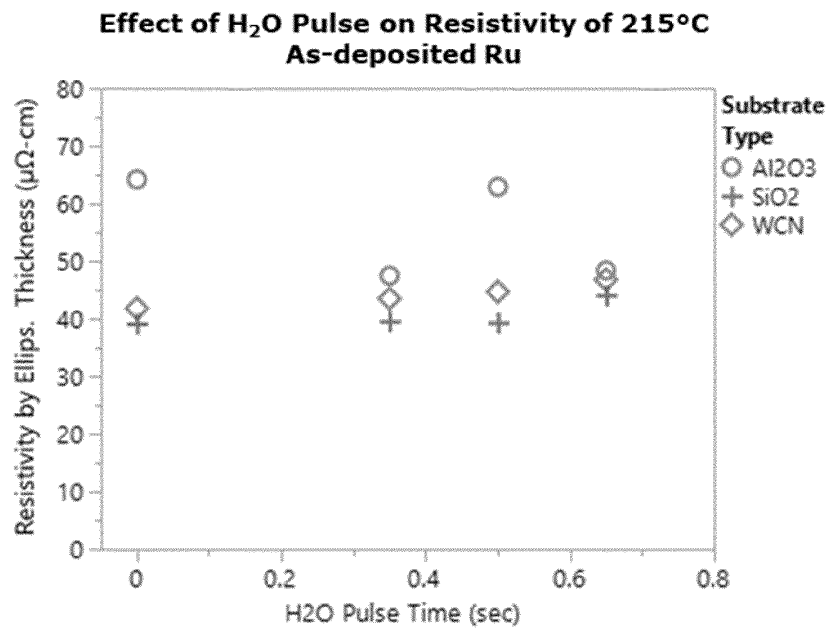


FIG. 2B

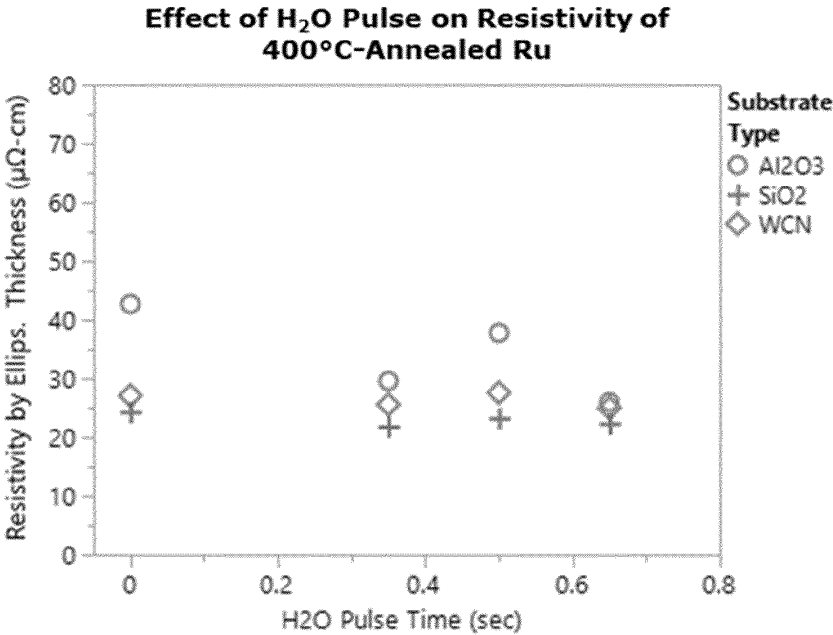


FIG. 2C

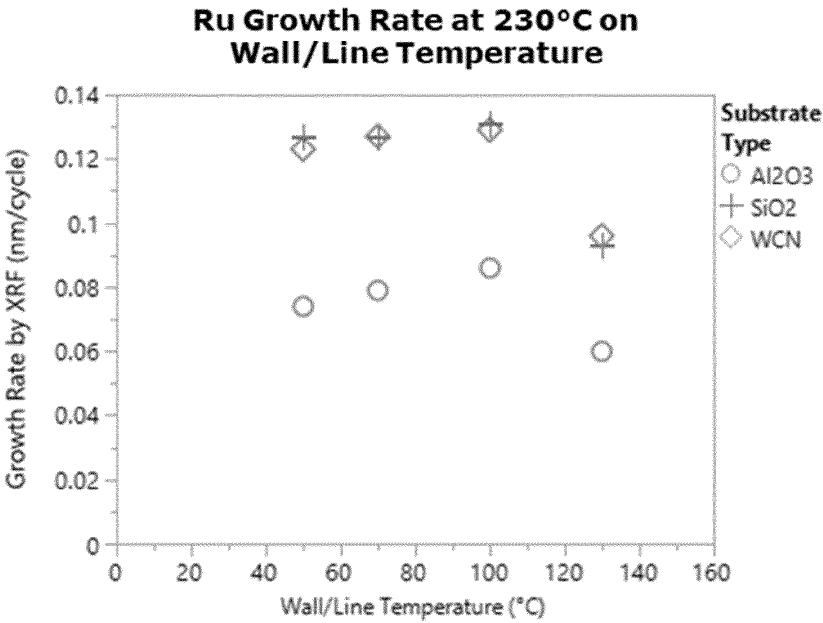


FIG. 3A

4/12

Dependence of Ru Resistivity on Wall/Line Temperature

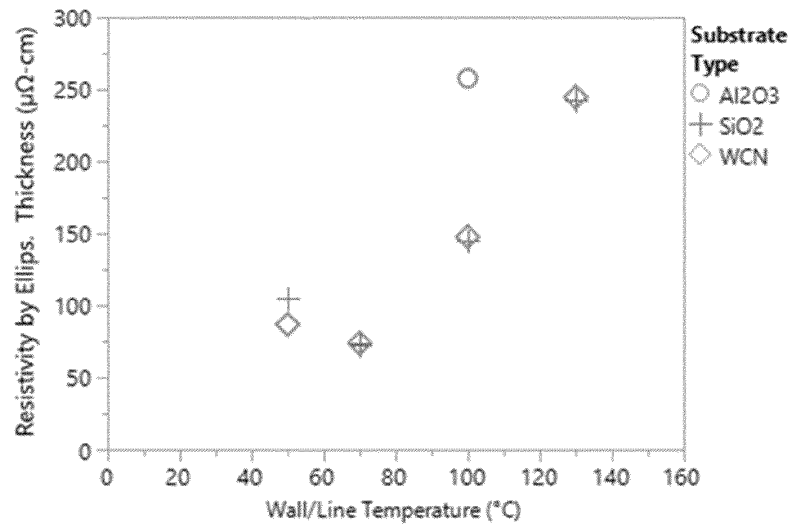


FIG. 3B

Change in Ru Growth Rate with Purge Time at 215 °C on Various Substrates

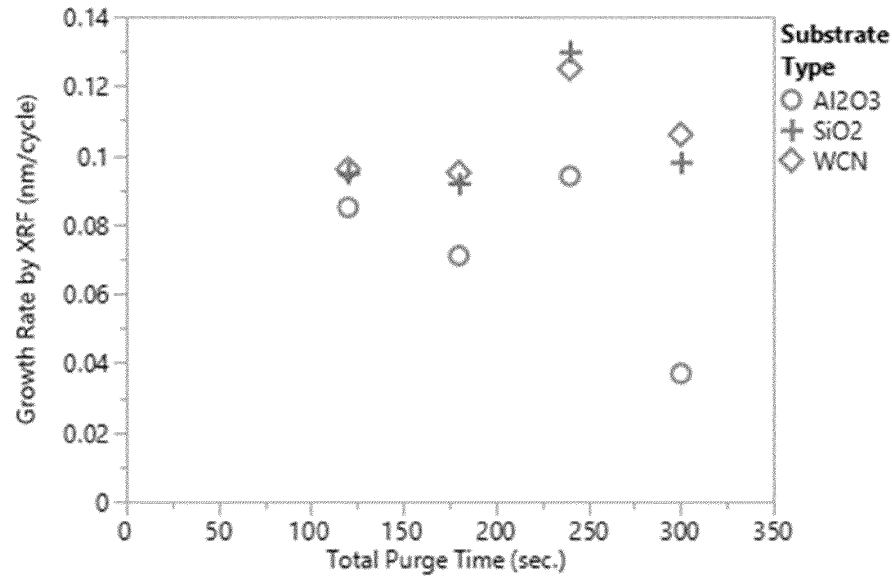


FIG. 4

5/12

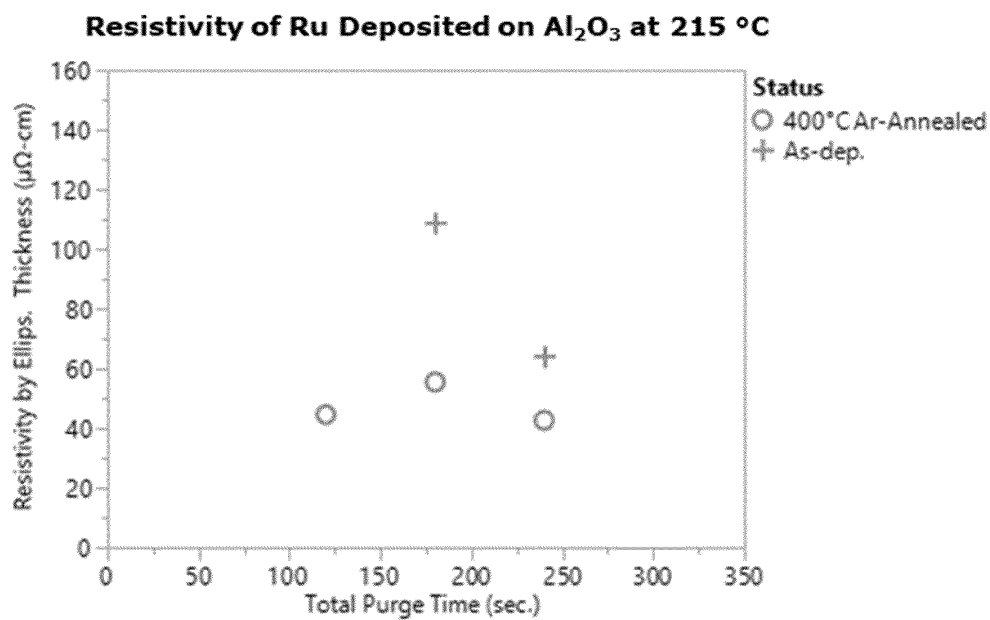


FIG. 5A

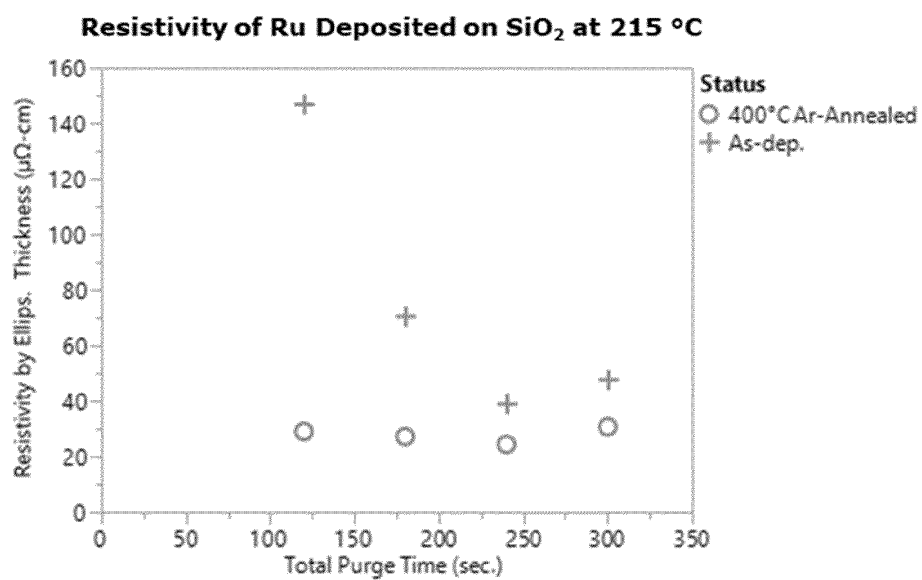


FIG. 5B

6/12

Resistivity of Ru Deposited on WCN at 215 °C

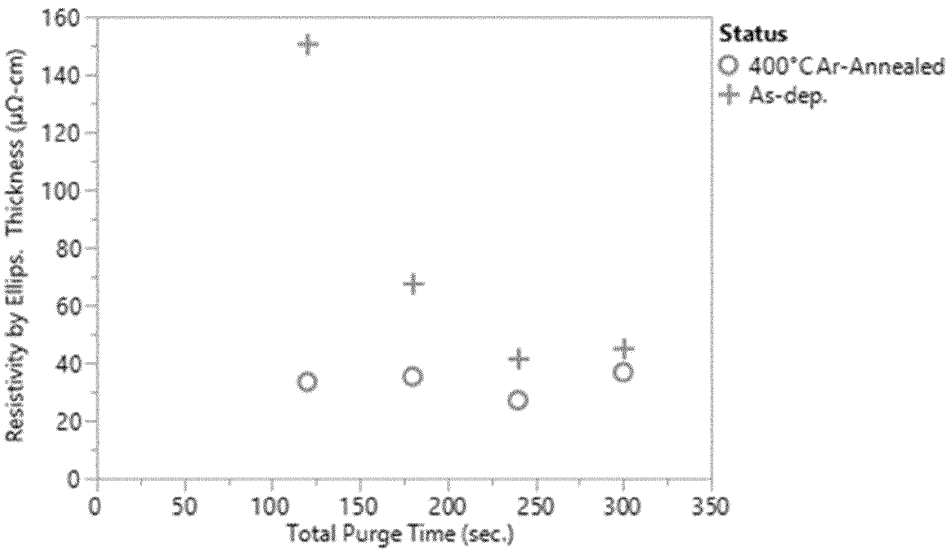


FIG. 5C

Saturation Behavior of Ru Growth Rate at 215 °C

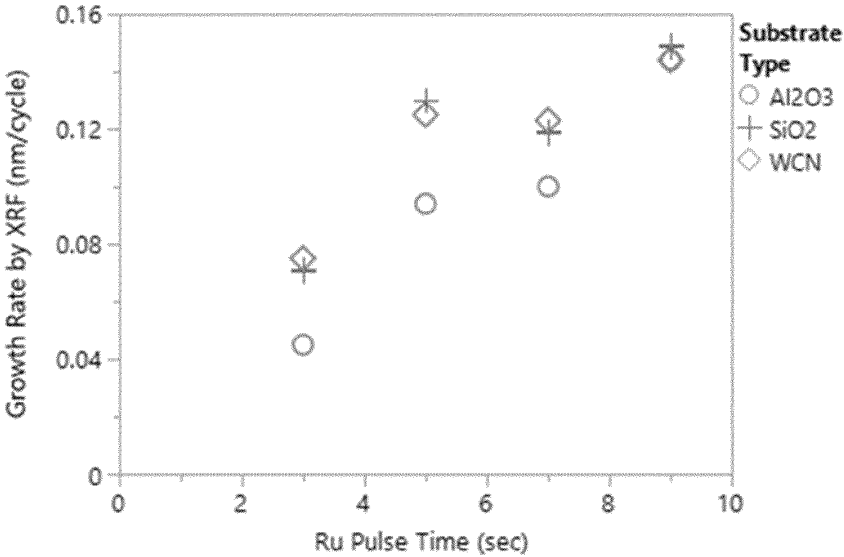


FIG. 6A

7/12

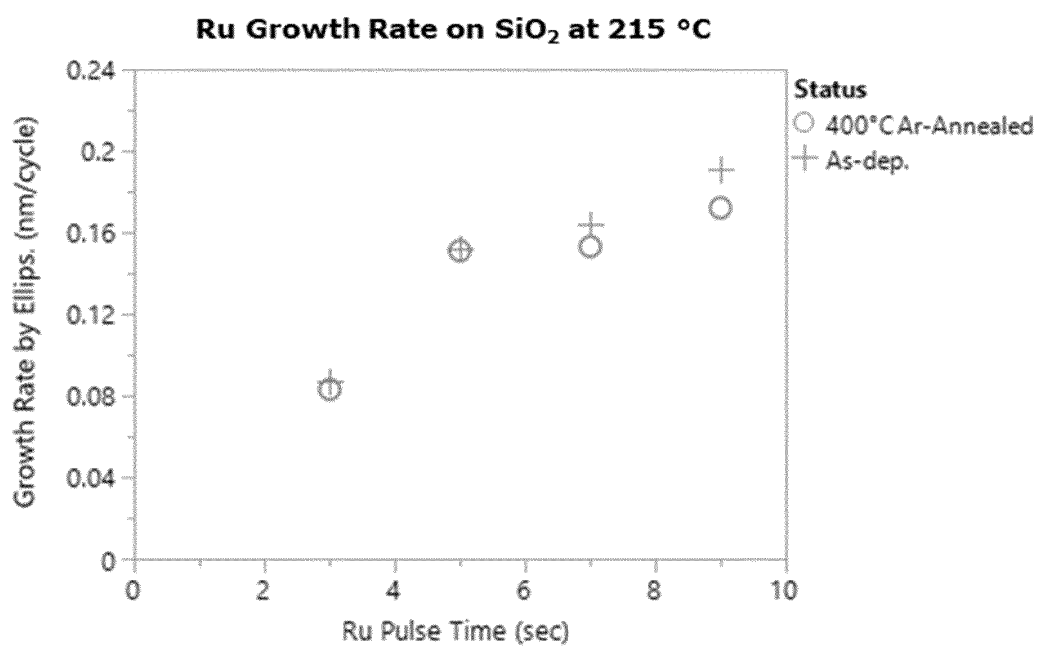


FIG. 6B

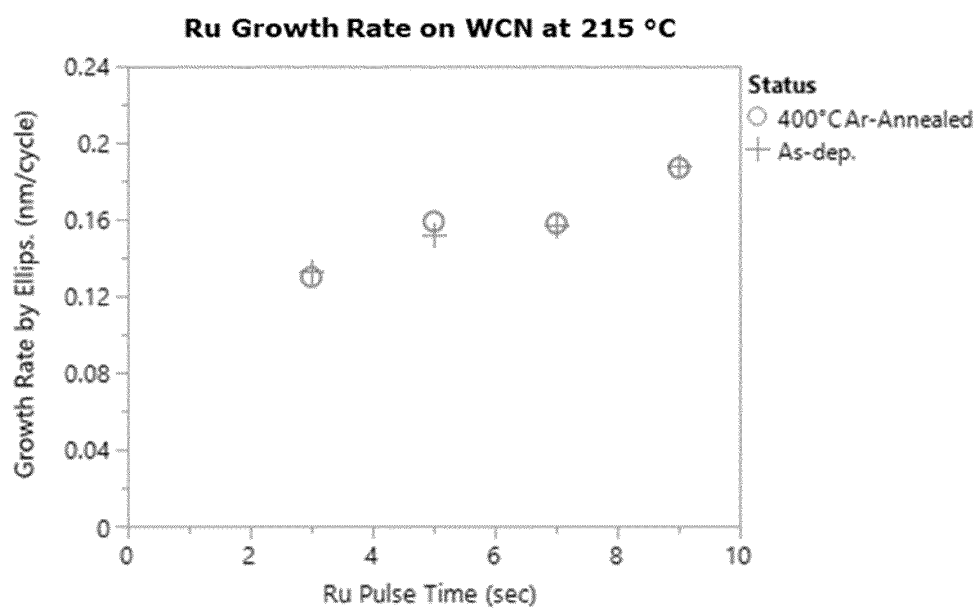


FIG. 6C

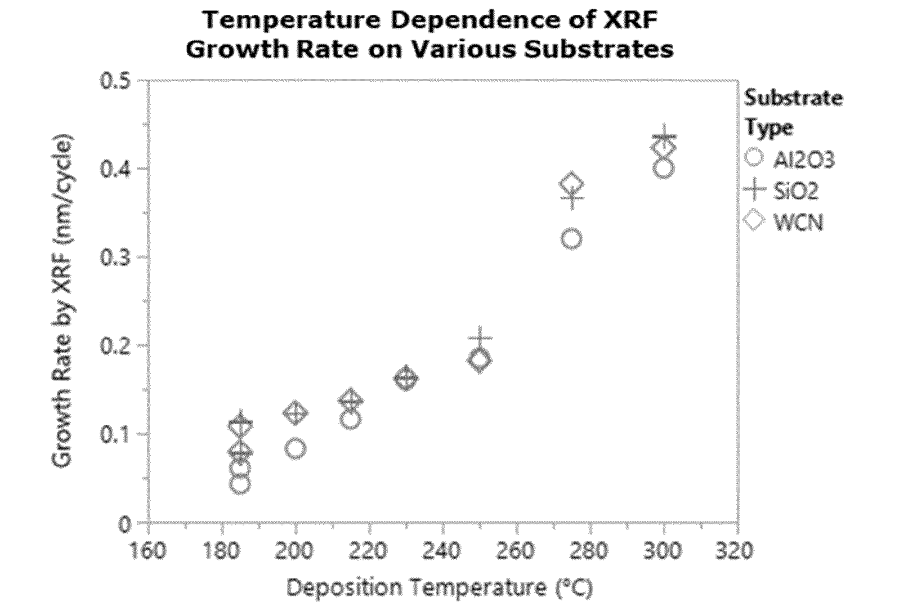


FIG. 7A

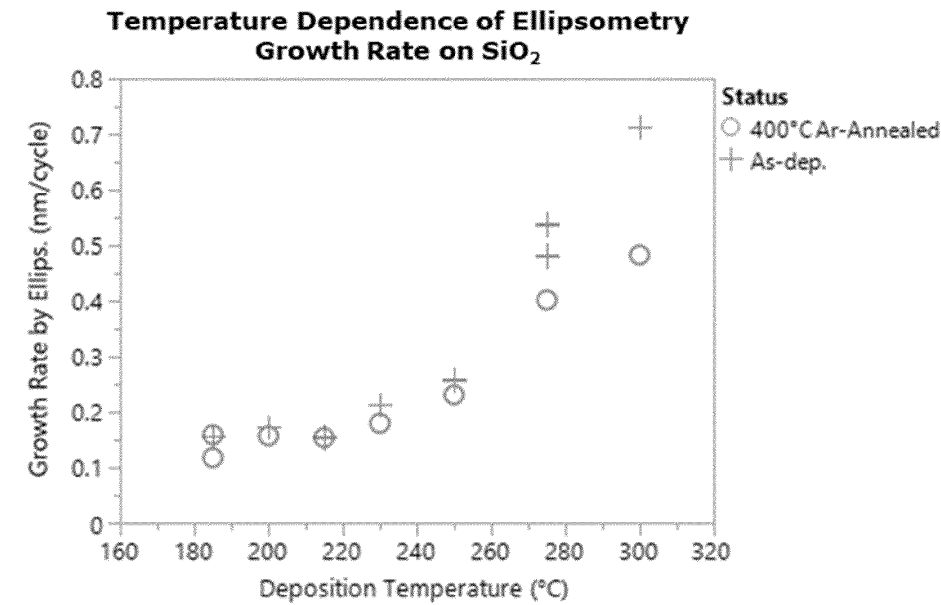


FIG. 7B

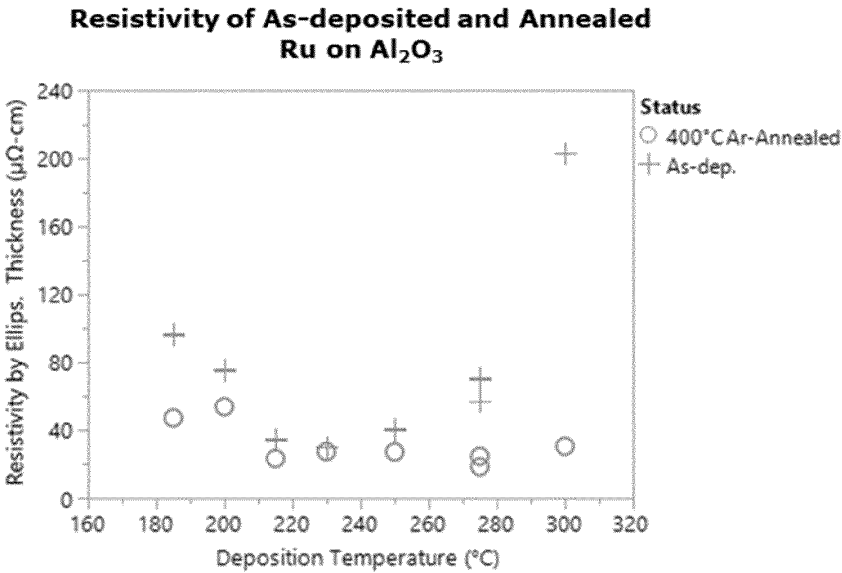


FIG. 8A

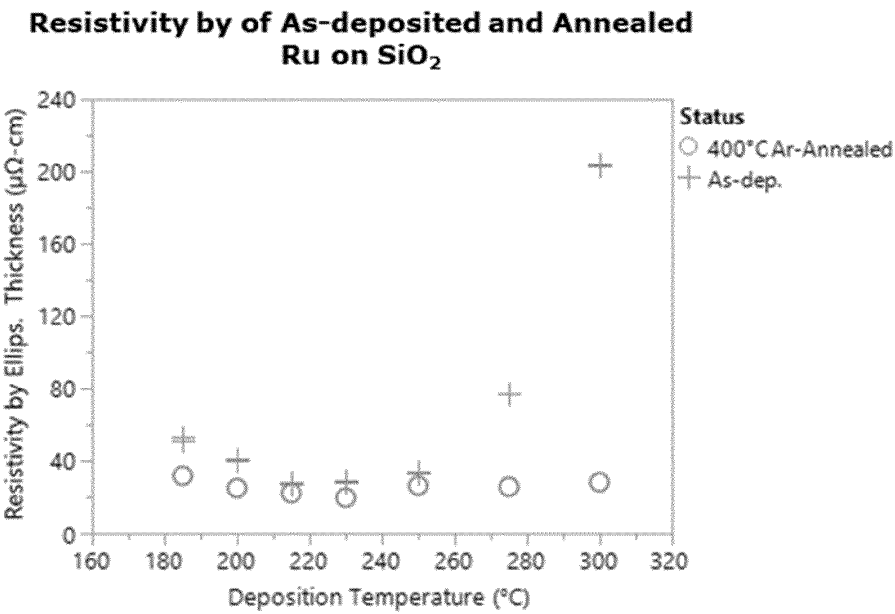


FIG. 8B

Resistivity by of As-deposited and Annealed
Ru on WCN

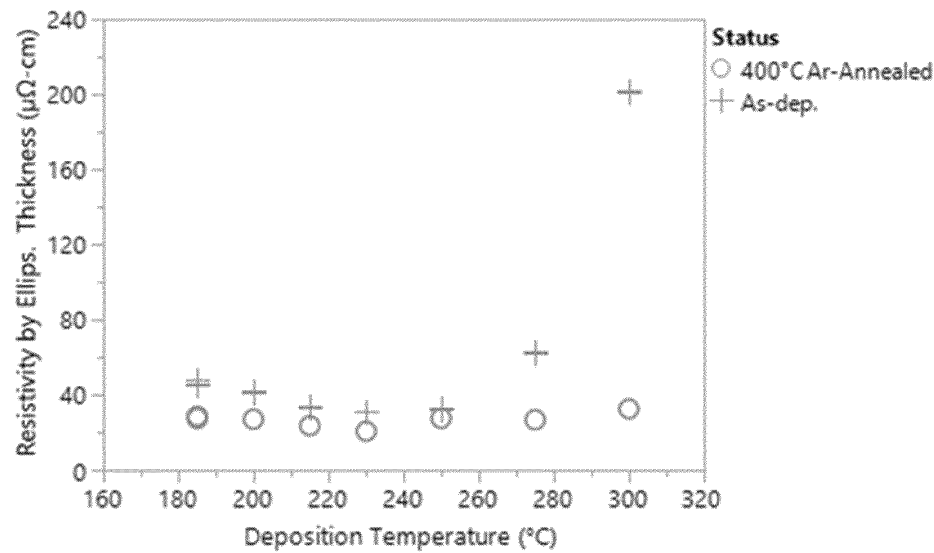


FIG. 8C

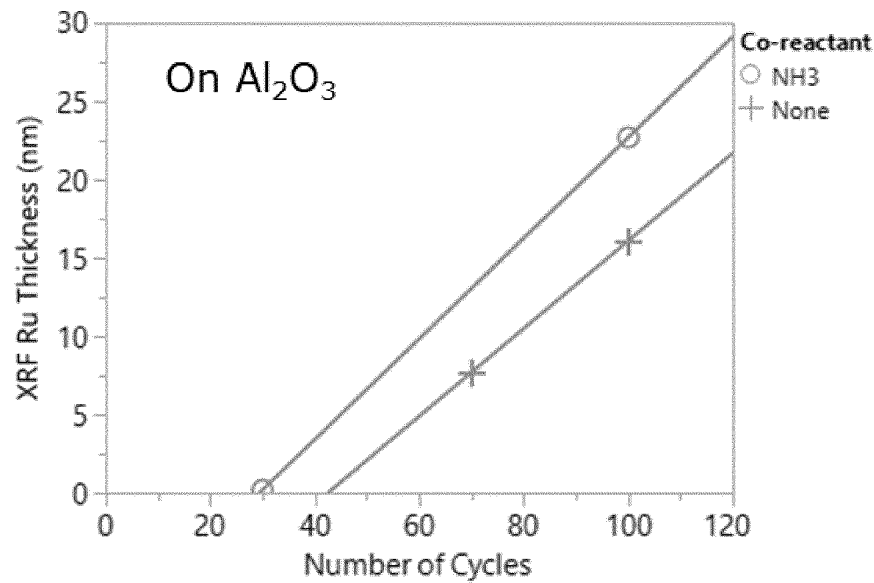


FIG. 9A

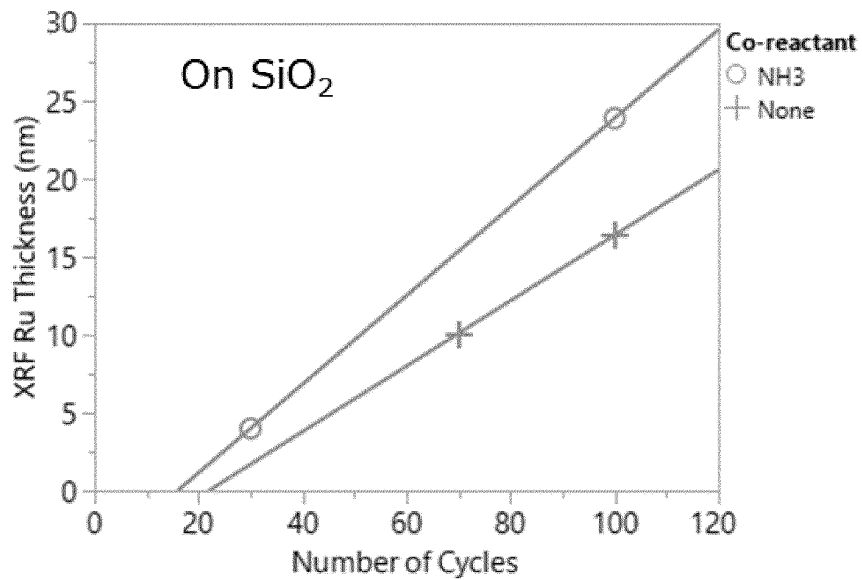


FIG. 9B

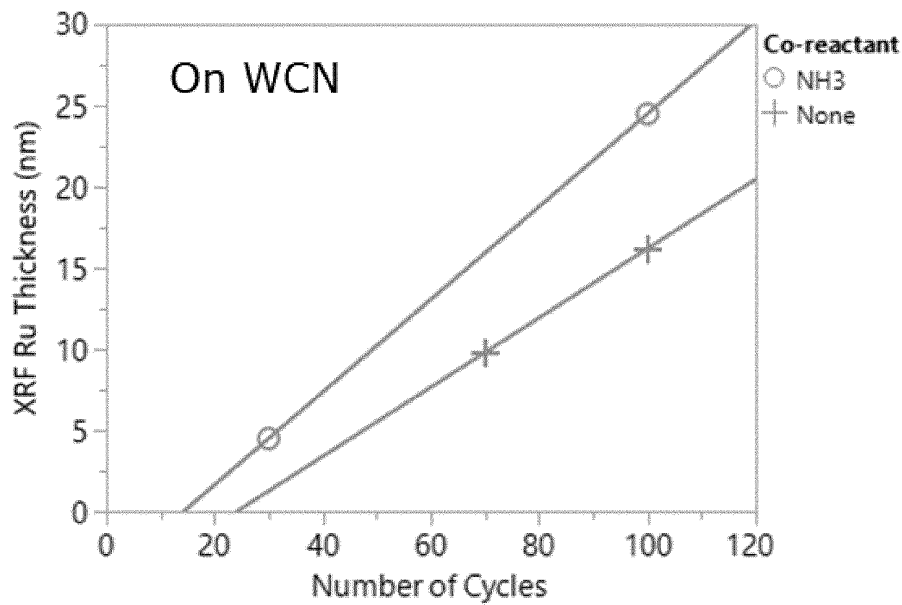


FIG. 9C

12/12

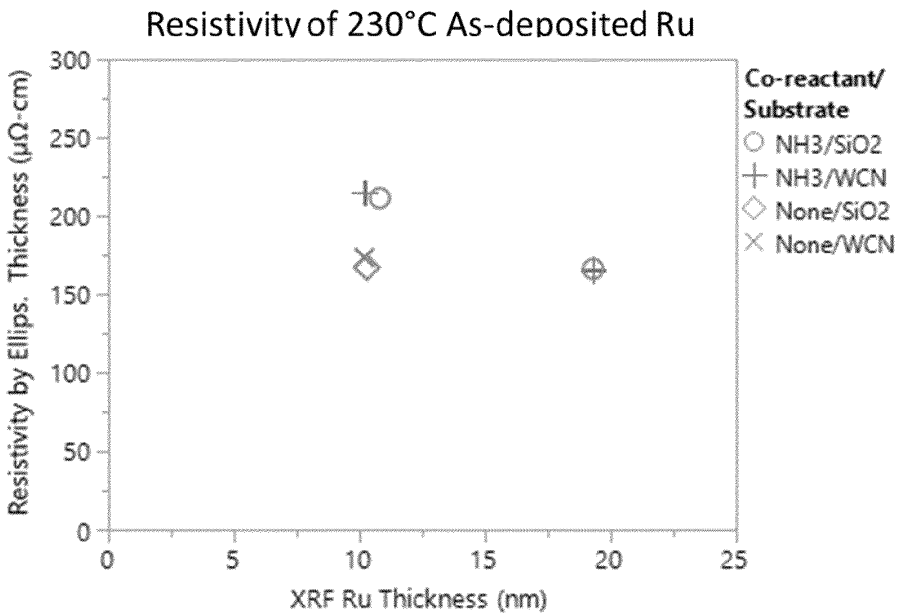


FIG. 10A

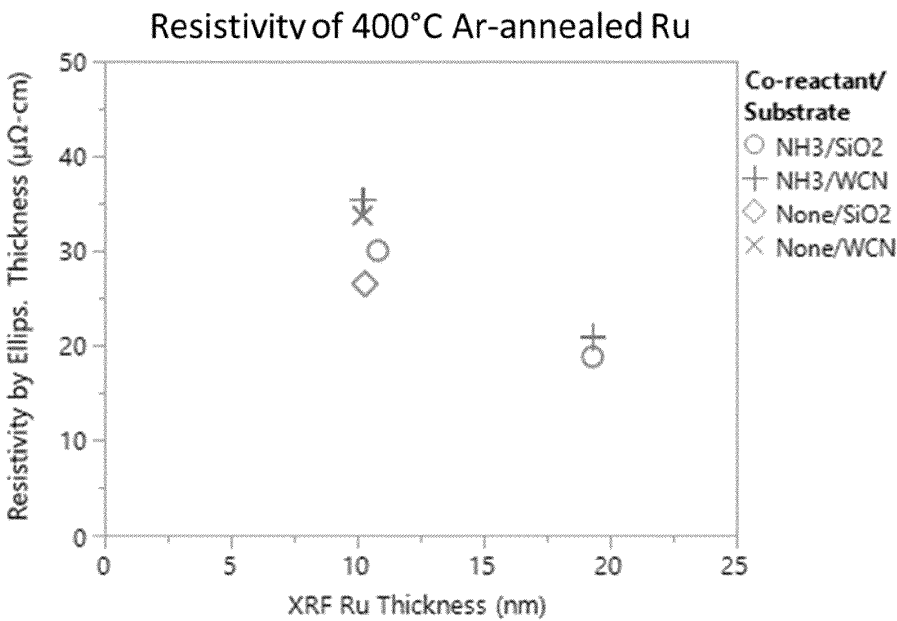


FIG. 10B